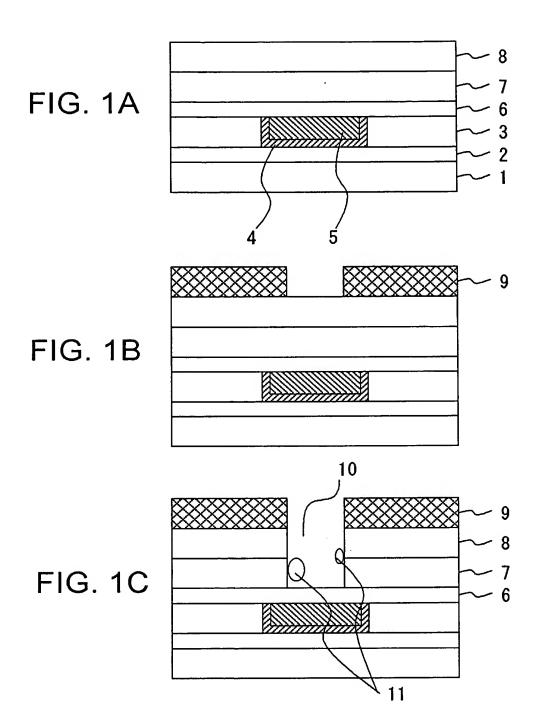
App No.: Not Yet Assigned Docket No.: P8375.0 Inventor: Hidemitsu Aoki, et al.

Title: METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE AND APPARATUS FOR CLEANING SUBSTRATE

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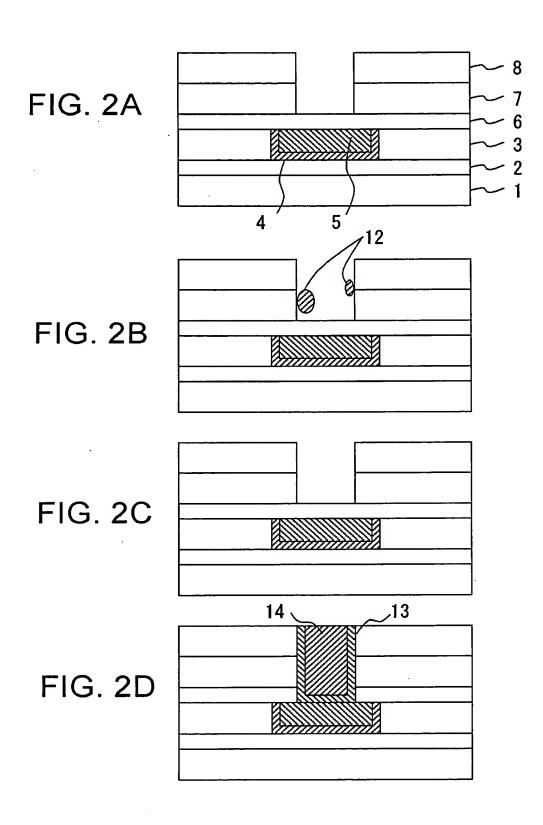


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Title: METHOD OF MANUFACTURING SEMICONDUCTOR Docket No.: P8375.0002

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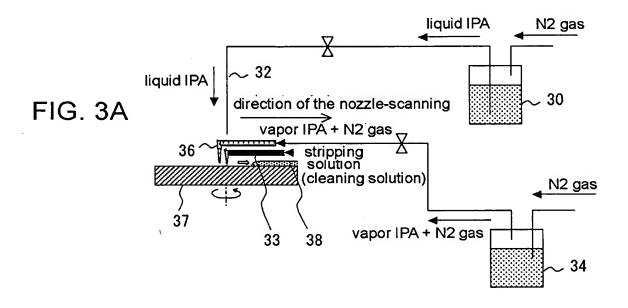


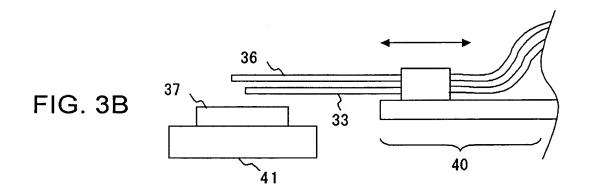
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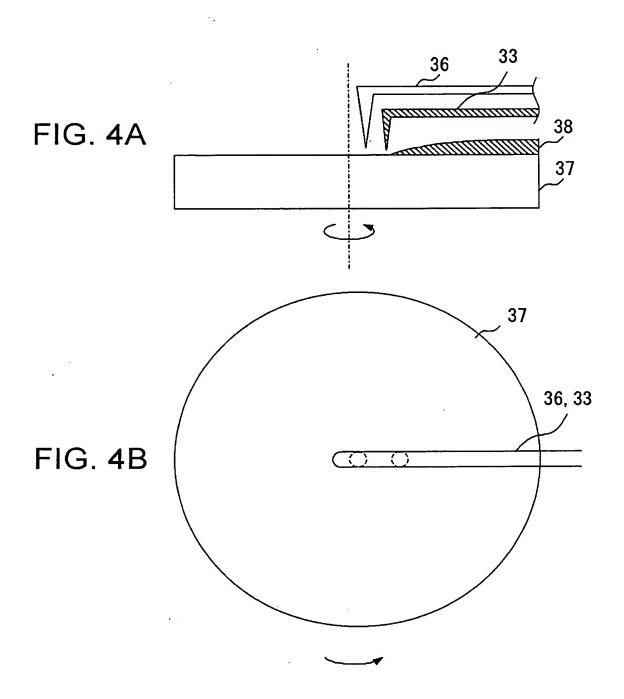
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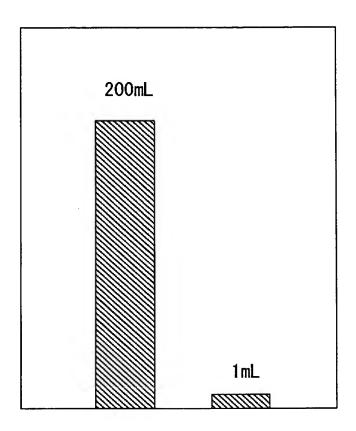
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FIG. 5

AMOUNTS OF **CONSUMED IPA** PER ONE WAFER



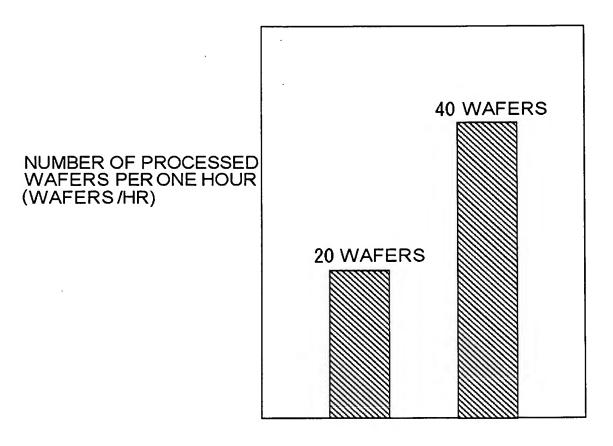
CONC. IPA **VAPOR IPA RINSE DRYING**

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FIG. 6



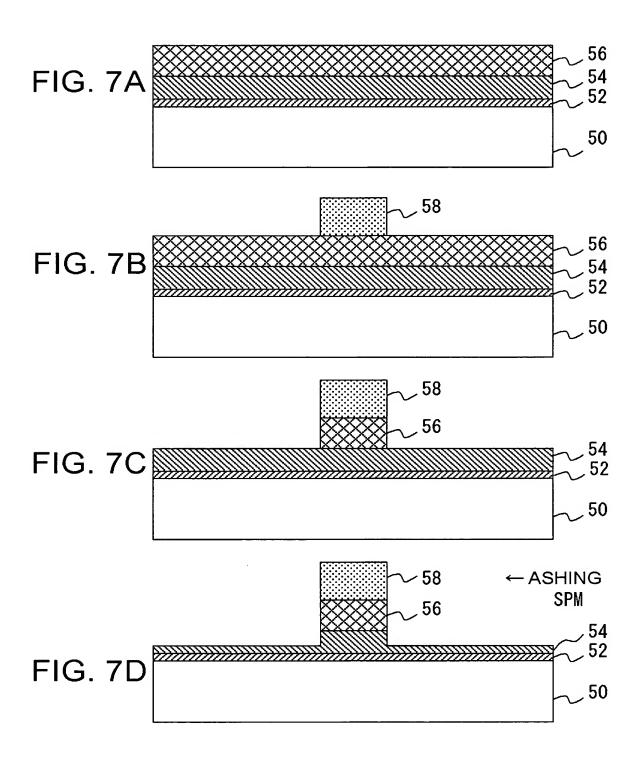
PURE WATER RINSE

VAPOR IPA DRYING

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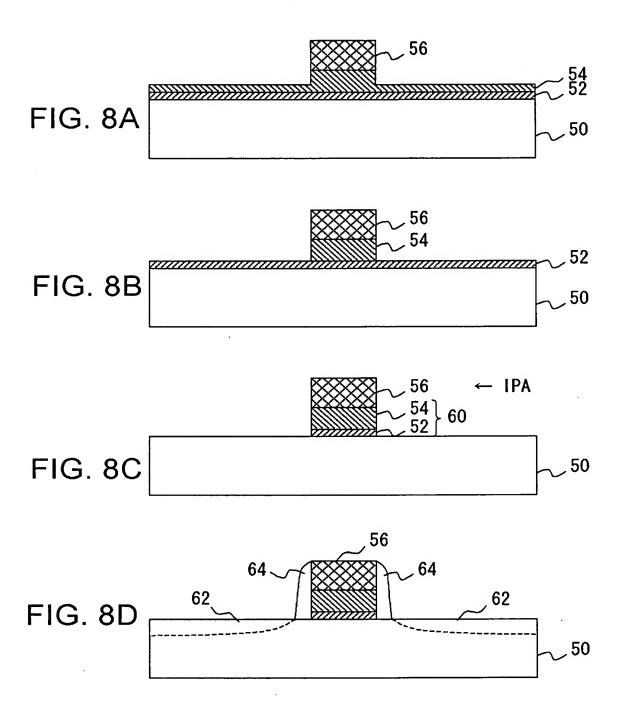
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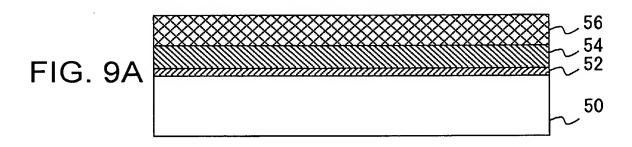
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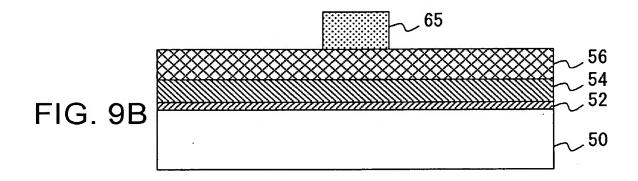


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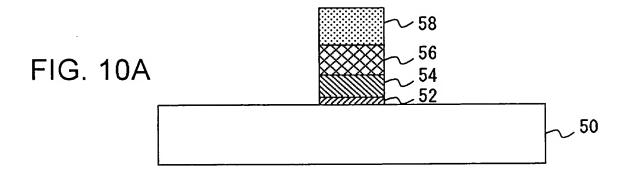


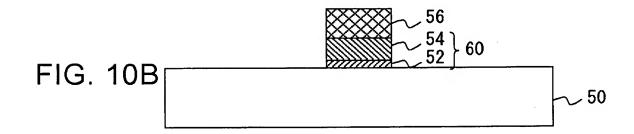


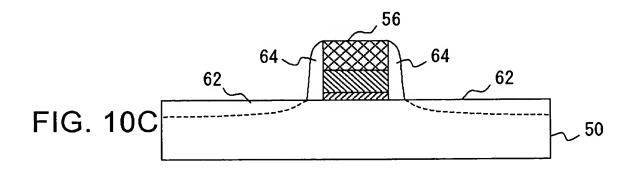
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Fig. 11A

	stripping agent	ı	liquid IPA	nozzle scanning vapor IPA + Ilquid	vapor IPA +	nozzle scanning vapor IPA drying	N ₂ gas dry (spinning drying)
No. 1 (Comparative Example)	1	2					3
No. 2	1		2				· 3

Fig. 11B

	stripping agent	 liquid IPA	1	vapor IPA +	N ₂ gas dry (spinning drying)
No.3(Comparative Example)	1		2 (DIW)		 3
No. 4	1			2	3

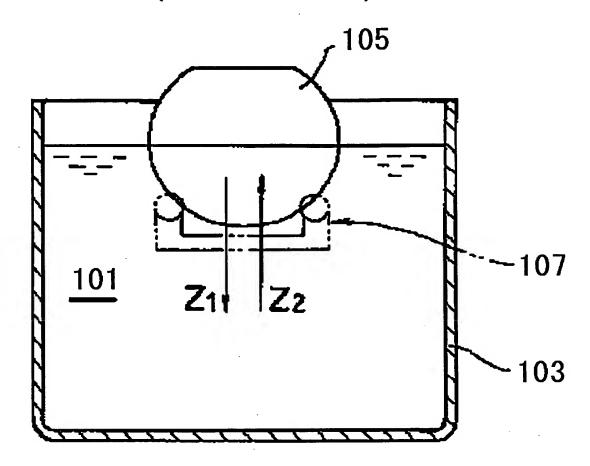
Fig. 11C

1 lg. 1 lO							
	stripping agent	pure water rinse	1 ' '	nozzle scanning vapor IPA + liquid	vapor IPA +	nozzle scanning vapor IPA drying	N ₂ gas dry (spinning drying)
No. 5(Comparative Example)	1	2				3	<u> </u>
No. 6	1		2			3	
No. 7	1				2	3	
No. 8	1		2			3	4
No. 9	1			2(electrolyte- containing water)			3

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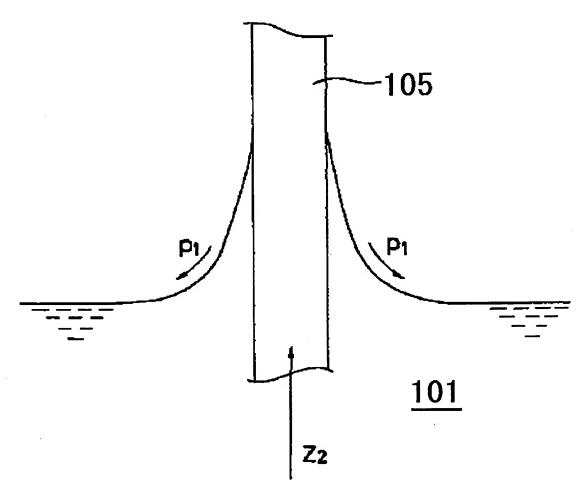
12/14 FIG. 12 (PRIOR ART)



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FIG. 13 (PRIOR ART)



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FIG. 14A

upper surface



FIG. 14B

